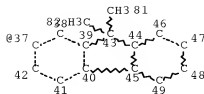
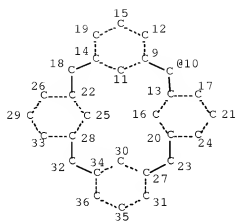


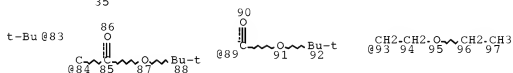
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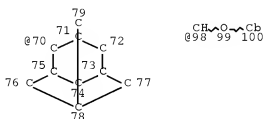
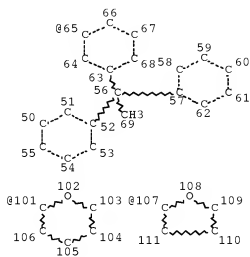
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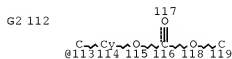
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Page 1-A

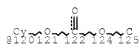
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123



G2 112

Page 2-A

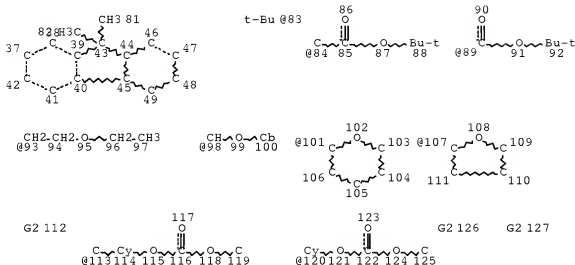


Page 3-A

VAR G1=10/37/65/70
 VAR G2=83/89/93/98/101/107/113/120/84
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 NSPEC IS RC AT 119
 NSPEC IS RC AT 125
 DEFAULT MLEVEL IS ATOM
 DEFAULT ELEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RSPEC I
 NUMBER OF NODES IS 117

STEREO ATTRIBUTES: NONE
 L4 33354 SEA FILE=REGISTRY SSS FUL L3
 L5 STR



VAR G2=83/89/93/98/101/107/113/120/84
 NODE ATTRIBUTES:
 NSPEC IS RC AT 119
 NSPEC IS RC AT 125
 DEFAULT MLEVEL IS ATOM
 DEFAULT ELEVEL IS LIMITED

GRAPH ATTRIBUTES:
 RSPEC I
 NUMBER OF NODES IS 60

STEREO ATTRIBUTES: NONE
 L7 52 SEA FILE=REGISTRY SUB=L4 SSS FUL L5
 L8 319 SEA FILE=REGISTRY ABB=ON PLU=ON C13H10/MF
 L9 570 SEA FILE=REGISTRY ABB=ON PLU=ON C15H14/MF
 L10 129991 SEA FILE=REGISTRY ABB=ON PLU=ON 1839.6/RID
 L11 74 SEA FILE=REGISTRY ABB=ON PLU=ON (L8 OR L9) AND L10
 L12 4 SEA FILE=REGISTRY ABB=ON PLU=ON L11 AND 9,9-DIMETHYL?
 L13 3 SEA FILE=REGISTRY ABB=ON PLU=ON L12 NOT T/ELS
 L18 1 SEA FILE=REGISTRY ABB=ON PLU=ON FLUORENE/CN
 L20 37 SEA FILE=HCAPLUS ABB=ON PLU=ON L7
 L23 873 SEA FILE=REGISTRY ABB=ON PLU=ON C13H10O3/MF
 L24 6 SEA FILE=REGISTRY ABB=ON PLU=ON L23 AND L10

10/531,208

L25 1 SEA FILE=REGISTRY ABB=ON PLU=ON L24 AND 9H-FLUORENETRIOL

L26 1 SEA FILE=REGISTRY ABB=ON PLU=ON L13 NOT RADICAL?

L27 13783 SEA FILE=HCAPLUS ABB=ON PLU=ON L26 OR L25 OR L18

L28 27 SEA FILE=HCAPLUS ABB=ON PLU=ON L27 AND (PHOTORESIST? OR
PHOTO RESIST? OR LIGHTRESIST? OR LIGHT RESIST?)

L29 14 SEA FILE=HCAPLUS ABB=ON PLU=ON L28 AND PHOTOG?/SC,SX

L31 7 SEA FILE=HCAPLUS ABB=ON PLU=ON L20 AND PHOTOG?/SC,SX

L36 12 SEA FILE=REGISTRY ABB=ON PLU=ON L7 NOT N/ELS

L37 10 SEA FILE=HCAPLUS ABB=ON PLU=ON L36

L38 2 SEA FILE=HCAPLUS ABB=ON PLU=ON L37 AND L31

L39 24 SEA FILE=HCAPLUS ABB=ON PLU=ON L29 OR L37

L40 24 SEA FILE=HCAPLUS ABB=ON PLU=ON L38 OR L39

=> D L40 1-24 IBIB ED ABS HITSTR HITIND

L40 ANSWER 1 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2008:1276428 HCAPLUS Full-text

DOCUMENT NUMBER: 149:481924

TITLE: Biphenyl derivatives and organic
electroluminescent devices therewith showing high
efficiency and luminescent intensity

INVENTOR(S): Abe, Shigemoto; Senoo, Akihiro; Kamatani, Atsushi;
Igawa, Satoshi; Yamada, Naoki

PATENT ASSIGNEE(S): Canon Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 28pp.
CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

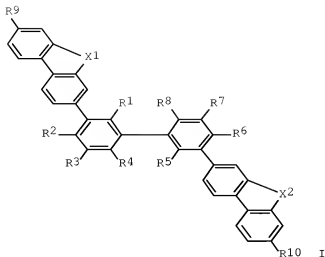
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2008255074	A	20081023	JP 2007-101489	20070409
PRIORITY APPLN. INFO.:			JP 2007-101489	20070409

ED Entered STN: 23 Oct 2008

GI



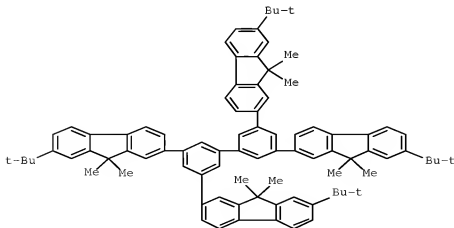
AB Biphenyl derivs. I [R1, R2, R4-R6, R8, R10 = H, (aryl)alkyl, alkenyl, alkynyl, alkoxy; R3, R7 = H, alkyl, aryl, heterocycle; X1, X2 = CR11R12, NR11 (R11, R12 = H, alkyl, aralkyl, aryl, heterocycle, halo)], and organic LED containing the same in host-guest-type emitting layers are sep. claimed. Thus, II (I; R1, R2, R4-R6, R8, R10 = H; X1, X2 = CMe2; R3, R7 = 9,9-dimethylfluoren-2-yl) was prepared from 3,3',5,5'-tetrabromobiphenyl and 2-(4,4,5,5-tetramethyl-1,3,2-dioxaborolan-2-yl)-9,9-dimethyl-9H-fluorene in the presence of Pd(PPh3)4 in 25.4% yield. An organic LED containing II and tris(2-phenylpyridine)iridium in a host-guest-type emitting layer was fabricated.

IT 1071808-04-2

(fluorenyl- or carbazolyl-substituted biphenyl derivs. giving organic electroluminescent devices with high intensity and efficiency)

RN 1071808-04-2 HCAPLUS

CN INDEX NAME NOT YET ASSIGNED

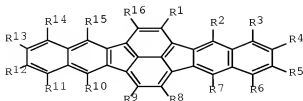


CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
 Section cross-reference(s): 25
 IT 1071808-04-2 1071808-05-3 1071808-06-4 1071808-09-7
 (fluorenyl- or carbazolyl-substituted biphenyl derivs. giving organic electroluminescent devices with high intensity and efficiency)

L40 ANSWER 2 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 2008:1127993 HCAPLUS Full-text
 DOCUMENT NUMBER: 149:366002
 TITLE: Fused ring aromatic compound and organic light-emitting devices using the aromatic compound as emitting dopant
 INVENTOR(S): Igawa, Satoshi; Hashimoto, Masashi; Okada, Shinjiro; Takiguchi, Takao; Okinaka, Keiji
 PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
 SOURCE: PCT Int. Appl., 67pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2008111540	A1	20080918	WO 2008-JP54222	20080303
W: AE, AG, AL, AM, AO, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, NO, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM JP 2008255095 A 20081023 JP 2008-23231 20080201 PRIORITY APPLN. INFO.: JP 2007-60609 A 20070309 JP 2008-23231 A 20080201				

ED Entered STN: 19 Sep 2008
 GI



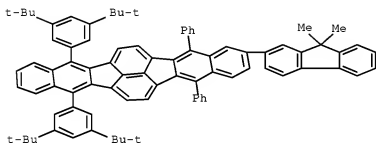
I

AB There are provided a novel fused ring aromatic compound represented by the general formula (I) and an organic light-emitting device which has an optical output with extremely high efficiency and luminance, and also has extremely high durability; where R1-16 each represent, independently of one another, a hydrogen atom, an alkyl group, a substituted or unsubstituted aralkyl group, a substituted or unsubstituted aryl group, a substituted or unsubstituted heterocyclic group, a substituted amino group, or a halogen atom; provided that at least one of combinations of R1 and R9, R2 and R10, R3 and R11, R4 and R12, R5 and R13, R6 and R14, R7 and R15, and R8 and R16, is a combination of different substituents.

IT 1058142-67-8P
(fused ring aromatic compound and organic green-emitting devices using the aromatic compound as emitting dopant)

RN 1058142-67-8 HCAPLUS

CN INDEX NAME NOT YET ASSIGNED



CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
Section cross-reference(s): 25, 76

IT 1058142-67-8P
(fused ring aromatic compound and organic green-emitting devices using the aromatic compound as emitting dopant)

REFERENCE COUNT: 7 THERE ARE 7 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L40 ANSWER 3 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2008:619943 HCAPLUS [Full-text](#)

DOCUMENT NUMBER: 148:596158

TITLE: Pyrene compound and organic light emitting device

INVENTOR(S): Suzuki, Koichi; Yamada, Naoki; Ueno, Kazunori

PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan

SOURCE: U.S. Pat. Appl. Publ., 25pp.
CODEN: USXXCO

DOCUMENT TYPE: Patent

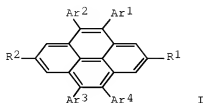
LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 20080119671	A1	20080522	US 2007-937115	20071108
JP 2008127291	A	20080605	JP 2006-310898	20061117
PRIORITY APPLN. INFO.:			JP 2006-310898	A 20061117

OTHER SOURCE(S): CASREACT 148:596158
 ED Entered STN: 23 May 2008
 GI



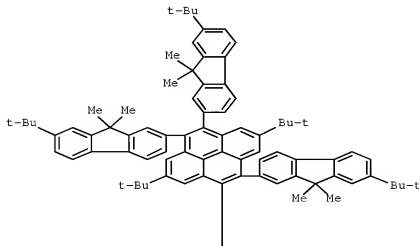
AB The title pyrene compds. are described by the general formula I (R1 and R2 = independently selected (un)substituted alkyl; and Ar1-4 = independently selected (un)substituted aryl, (un)substituted heterocyclic, (un)substituted condensed polycyclic aromatic, and (un)substituted condensed polycyclic heterocyclic). Organic light-emitting devices with layers including the compds., inks containing the compds. (which are suitable for forming the layers), and display devices employing the light-emitting devices are also described.

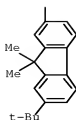
IT 1027059-55-7
 (pyrene derivs. and organic light-emitting devices and inks containing them and display devices using the light-emitting devices)

RN 1027059-55-7 HCAPLUS

CN Pyrene, 2,7-bis(1,1-dimethylethyl)-4,5,9,10-tetrakis[7-(1,1-dimethylethyl)-9,9-dimethyl-9H-fluoren-2-yl]- (CA INDEX NAME)

PAGE 1-A





INCL 564308000; 313504000; 564307000; 585027000

CC 73-5 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

Section cross-reference(s): 25, 74, 76

IT 1027059-55-7 1027059-56-8 1027059-57-9 1027059-58-0
 1027059-62-6 1027059-64-8 1027059-65-9 1027059-69-3
 1027059-70-6 1027059-74-0 1027059-77-3 1027059-81-9
 1027059-83-1 1027059-85-3 1027059-87-5 1027059-89-7
 1027059-90-0 1027059-91-1 1027059-93-3 1027059-96-6
 1027059-98-8 1027211-56-8 1027211-57-9

(pyrene derivs. and organic light-emitting devices and inks containing them and display devices using the light-emitting devices)

L40 ANSWER 4 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2008:546174 HCAPLUS Full-text

DOCUMENT NUMBER: 149:115130

TITLE: Improving the Luminance Properties of BGOLED by Using Hole Blocking and Energy Transfer
 AUTHOR(S): Yang, Su-Hua; Chang, Wen-Kai; Hong, Bo-Cheng; Huang, Xian-Bi

CORPORATE SOURCE: Department of Electronic Engineering, National Kaohsiung University of Applied Sciences, Kaohsiung, Taiwan

SOURCE: Journal of the Electrochemical Society (2008), 155(6), J161-J164

CODEN: JESQAN; ISSN: 0013-4651

PUBLISHER: Electrochemical Society

DOCUMENT TYPE: Journal

LANGUAGE: English

ED Entered STN: 07 May 2008

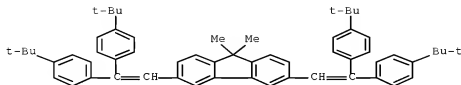
AB A high-luminance blue-green organic light-emitting diode (BGOLED) based on a single LT-N421:C6 [3-(2-Benzothiazolyl)-7-(diethylamino)coumarin] emitting layer along with a 4,4'-bis(2,2-diphenyl-ethen-1-yl)-diphenyl (DPVBi) hole-blocking layer was fabricated. The structure of the BGOLED was In Sn oxide/N, N'-di(naphthalene-1-yl)-N, N'-diphenyl-benzidine (NPB, 50 nm)/LT-N421:C6 (32 nm)/DPVBi (8 nm)/tris-(8-hydroxy-quinolinato)-Al (Alq3, 20 nm)/LiF (1 nm)/Al (200 nm). The DPVBi layer inserted between the LT-N421:C6 and Alq3 layers reduced the interface barrier for electron injection and blocked holes in the emitting layer to increase the electron-hole recombination. The electroluminescence of LT-N421 was quenched by C6 dopant and the exciton energy was efficiently transferred from LT-N421 to C6, which resulted in the blue-green C6 dominant emission. The optimum deposition rate ratio of C6 to LT-N421 was 0.4%. The maximum luminance was 42,400 cd/m² at 11 V. The current and power efficiencies were 8.83 cd/A at 11 V and 3.96 lm/W at 6 V, resp.

IT 1034543-32-2

(improving the luminance properties of BGOLED by using hole blocking and energy transfer)

RN 1034543-32-2 HCAPLUS

CN 9H-Fluorene, 3,6-bis[2,2-bis[4-(1,1-dimethylethyl)phenyl]ethenyl]-9,9-dimethyl- (CA INDEX NAME)



CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

IT 2085-33-8, Aluminum tris(8-hydroxyquinolino) 38215-36-0, Coumarin 6 123847-85-8, NPB 142289-08-5, DPVBi 1034543-32-2

(improving the luminance properties of BGOLED by using hole blocking and energy transfer)

REFERENCE COUNT: 14 THERE ARE 14 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L40 ANSWER 5 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2008:159511 HCAPLUS Full-text

DOCUMENT NUMBER: 148:249688

TITLE: Fused heterocyclic compounds and organic light-emitting devices using them

INVENTOR(S): Ohnui, Hiroki; Okada, Shinjiro; Senoo, Akihiro; Yamada, Naoki; Muratsubaki, Masanori

PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan

SOURCE: PCT Int. Appl., 210pp.

CODEN: PIXXD2

DOCUMENT TYPE: Patent

LANGUAGE: English

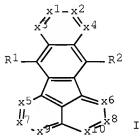
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2008016166	A1	20080207	WO 2007-JP65328	20070731
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DO, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, ME, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW				
RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM				

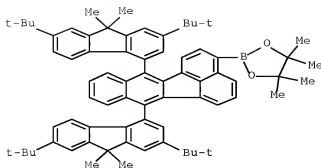
JP 2008056658	A	20080313	JP 2007-118218	20070427
PRIORITY APPLN. INFO.:			JP 2006-213063	A 20060804
			JP 2007-118218	A 20070427

OTHER SOURCE(S): MARPAT 148:249688
 ED Entered STN: 07 Feb 2008
 GI



AB Fused heterocyclic compound comprising ≥ 1 partial structure are described by the general formula I (X1-10 = independently selected CR or N; R = independently selected at each occurrence H, halo, (un)substituted alkyl, (un)substituted alkenyl, (un)substituted alkynyl, (un)substituted amino, (un)substituted aralkyl, (un)substituted aryl, (un)substituted heterocyclic, (un)substituted fused polycyclic aromatic, (un)substituted fused polycyclic heterocyclic, cyano, or a single bond with the restriction that ≥ 1 of X1-10 = N and adjacent Rs may form a ring structure; and R1-2 = IS halo, (un)substituted alkyl, (un)substituted alkenyl, (un)substituted alkynyl, (un)substituted amino, (un)substituted aralkyl, (un)substituted aryl, (un)substituted heterocyclic, (un)substituted fused polycyclic aromatic, (un)substituted fused polycyclic heterocyclic, cyano, or a single bond). Organic light-emitting devices are described which comprise an anode and a cathode, ≥ 1 of which is formed of a transparent or semitransparent electrode material with a layer containing a fused heterocyclic compound provided between them. Isonicotinonitrile.

IT 1013653-08-3
 (fused heterocyclic compds. and organic light-emitting devices using them)
 RN 1013653-08-1 HCAPLUS
 CN 1,3,2-Dioxaborolane, 2-[7,12-bis[2,7-bis(1,1-dimethylethyl)-9,9-dimethyl-9H-fluorene-4-yl]benzo[k]fluoranthene-3-yl]-4,4,5,5-tetramethyl-
 (CA INDEX NAME)



CC 73-5 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
 Section cross-reference(s): 27, 28, 76
 IT 98-98-6, Picolinic acid 1714-29-0 3029-19-4,
 1-Pyrenecarboxaldehyde 4964-71-0 13438-50-1 28440-63-3,
 3-Fluoranthene-9-carboxaldehyde 31462-59-6, 4-Pyrimidinecarboxylic acid
 34966-24-6 863878-53-9 1013652-96-4 1013652-98-6 1013653-07-0
 1013653-08-1
 (fused heterocyclic compds. and organic light-emitting devices using them)

REFERENCE COUNT: 13 THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

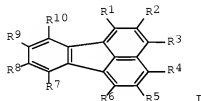
L40 ANSWER 6 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 2007:1274215 HCAPLUS [Full-text](#)
 DOCUMENT NUMBER: 147:511314
 TITLE: Fluoranthene derivative and organic light emitting device having the same
 INVENTOR(S): Hashimoto, Masashi; Saitoh, Akihito; Yamada, Naoki; Igawa, Satoshi; Kamatani, Jun; Takiguchi, Takao; Okada, Shinjiro
 PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
 SOURCE: PCT Int. Appl., 51pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2007126112	A1	20071108	WO 2007-JP59351	20070424
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BH, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW			
RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG,			

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ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM
 JP 2007314510 A 20071206 JP 2007-42663 20070222
 PRIORITY APPLN. INFO.: JP 2006-123783 A 20060427
 JP 2007-42663 A 20070222

OTHER SOURCE(S): MARPAT 147:511314
 ED Entered STN: 09 Nov 2007
 GI

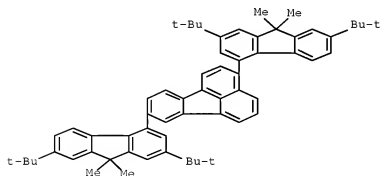


AB A fluoranthene derivative represented by the following general formula I is described where R1-R10 are each independently selected from a hydrogen atom, a halogen atom, a substituted amino group, a linear or branched alkyl group and other groups shown in the text. An organic light emitting device comprising the fluoranthene derivative is also described.

IT 955121-13-8P
 (fluoranthene derivative and organic light emitting device having same)

RN 955121-13-8 HCAPLUS

CN Fluoranthene, 3,8-bis[2,7-bis(1,1-dimethylethyl)-9,9-dimethyl-9H-fluoren-4-yl]- (CA INDEX NAME)



CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
 Section cross-reference(s): 25, 76

IT 955121-13-8P
 (fluoranthene derivative and organic light emitting device having same)

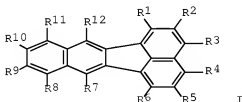
REFERENCE COUNT: 6 THERE ARE 6 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE

RE FORMAT

L40 ANSWER 7 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 2007:1145344 HCAPLUS Full-text
 DOCUMENT NUMBER: 147:458511
 TITLE: Novel compound and organic light emitting device
 using the compound
 INVENTOR(S): Igawa, Satoshi; Okada, Shinjiro; Kamatani, Jun;
 Yamada, Naoki; Hashimoto, Masashi; Okinaka, Keiji;
 Negishi, Chika; Saitoh, Akihito; Takiguchi, Takao
 PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan
 SOURCE: PCT Int. Appl., 104pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: English
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2007114038	A1	20071011	WO 2007-JP55583	20070313
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, GT, HN, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LA, LC, LK, LR, LS, LT, LU, LY, MA, MD, MG, MK, MN, MW, MX, MY, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RS, RU, SC, SD, SE, SG, SK, SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, ZA, ZM, ZW			
RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, MT, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			
JP 2007291061	A	20071108	JP 2006-334985	20061212
PRIORITY APPLN. INFO.:			JP 2006-99896	A 20060331
			JP 2006-334985	A 20061212

OTHER SOURCE(S): MARPAT 147:458511
 ED Entered STN: 11 Oct 2007
 GI



AB A mono(benzo[k]fluoranthene) compound represented by the general formula I, is described where R1-R12 each represent a hydrogen atom, a linear or branched alkyl group, a substituted or unsubstituted aryl group, or a substituted or unsubstituted heterocyclic group, provided that at least one of R7, R8, and R9

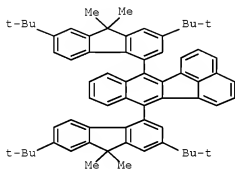
represents a substituted or unsubstituted condensed ring aromatic group which is tricyclic or more. An organic light emitting device is also described comprising at least a pair of electrodes formed of an anode and a cathode, and an light emitting layer formed of an organic compound, the layer being interposed between the pair of electrodes, in which the layer formed of the organic compound

IT 952141-67-2

(light emitting layer; benzofluoranthene derivative compound and organic light emitting device using the compound)

RN 952141-67-2 HCAPLUS

CN Benzo[k]fluoranthene, 7,12-bis[2,7-bis(1,1-dimethylethyl)-9,9-dimethyl-9H-fluoren-4-yl]- (CA INDEX NAME)



CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)

Section cross-reference(s): 24, 76

IT 952141-58-1 952141-59-2 952141-60-5 952141-61-6 952141-62-7

952141-63-8 952141-64-9 952141-65-0 952141-66-1

952141-67-2 952141-68-3 952141-69-4 952141-70-7

952141-71-8

(light emitting layer; benzofluoranthene derivative compound and organic light emitting device using the compound)

REFERENCE COUNT: 8 THERE ARE 8 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L40 ANSWER 8 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2007:1119993 HCAPLUS Full-text

DOCUMENT NUMBER: 147:436474

TITLE: Fluorene derivative and organic electroluminescent device using the fluorene derivative in a light-emitting layer

INVENTOR(S): Igawa, Satoshi; Okada, Shinjiro; Takiguchi, Takao; Hashimoto, Masashi; Yamada, Naoki

PATENT ASSIGNEE(S): Canon Kabushiki Kaisha, Japan

SOURCE: U.S. Pat. Appl. Publ., 33pp.

CODEN: USXXCO

DOCUMENT TYPE: Patent

LANGUAGE: English

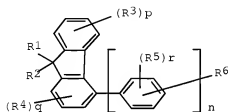
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO. KIND DATE APPLICATION NO. DATE

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US 20070232841	A1	20071004	US 2007-686002
JP 2007269736	A	20071018	JP 2006-99895
PRIORITY APPLN. INFO.:			JP 2006-99895
			A 20060331
			20070314
			20060331

OTHER SOURCE(S): MARPAT 147:436474
 ED Entered STN: 05 Oct 2007
 GI



I

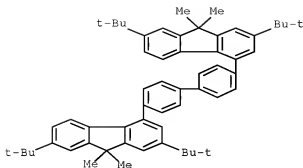
AB Fluorene derivs. are described which are represented by the following structural formula (I), where R1 and R2 each independently represent a hydrogen atom, an alkyl group, a substituted or unsubstituted aralkyl group, a substituted or unsubstituted aryl group, or a substituted or unsubstituted heterocyclic group; R3 and R4 each represent a linear, branched, or cyclic substituted or unsubstituted alkyl group; a substituted or unsubstituted aryl group; or a halogen atom, provided that, when R3 and R4 are each present in plurality, R3's may be identical to or different from each other, and R4's may be identical to or different from each other; p and r represent integers of 0 to 4, and q represents an integer of 0 to 3; R5 represents a linear, branched, or cyclic substituted or unsubstituted alkyl group; a halogen atom; or a substituted or unsubstituted aryl group, provided that, when R5 is present in plurality, R5's may be identical to or different from each other; when the phenylene group is present in plurality, the substituents R5's of phenylene groups may be identical to or different from each other, and the substituents R6's of phenylene groups may be identical to or different from each other; n represents an integer of 1 to 10; and R6 represents a hydrogen atom, a substituted or unsubstituted aryl group, or a linear, branched, or cyclic alkyl group. Organic electroluminescent devices are described which comprise a pair of electrodes, and at least one layer containing an organic compound interposed between the pair of the electrodes and containing the fluorene derivative as a host in a light-emitting layer.

IT 951400-23-0P

(fluorene derivative and organic electroluminescent device using the fluorene derivative as host in light-emitting layer)

RN 951400-23-0 HCAPLUS

CN 9H-Fluorene, 4,4'-[1,1'-biphenyl]-4,4'-diylbis[2,7-bis(1,1-dimethylethyl)-9,9-dimethyl- (CA INDEX NAME)



INCL -585; -428; -428; -313; -313; -257; 257-E51.049; 257-E51.044;
 257-E51.041
 CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related
 Properties)
 Section cross-reference(s): 22, 25, 76
 IT 951400-23-0P
 (fluorene derivative and organic electroluminescent device using the
 fluorene derivative as host in light-emitting layer)

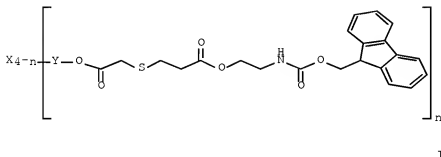
L40 ANSWER 9 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 2006:944672 HCAPLUS [Full-text](#)
 DOCUMENT NUMBER: 145:345245
 TITLE: Base multiplying agents and base-reactive curable
 compositions
 INVENTOR(S): Aoki, Kenichi; Ichimura, Kunihiro; Nagano, Motoi;
 Fukui, Hiroji
 PATENT ASSIGNEE(S): Sekisui Chemical Co., Ltd., Japan
 SOURCE: PCT Int. Appl., 27pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 2006095670	A1	20060914	WO 2006-JP304239	20060306
W: AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, KE, KG, KM, KN, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, LY, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW RW: AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM JP 2006282657 A 20061019 JP 2006-43517 20060221 JP 3884758 B2 20070221 DE 112006000540 T5 20080124 DE 2006-112006000540 20060306 CN 101137620 A 20080305 CN 2006-80007394 20070907 KR 2007113218 A 20071128 KR 2007-720647 20070910				

10/531,208

US 20080200580	A1	20080821	US 2007-885997	20070910
PRIORITY APPLN. INFO.:			JP 2005-70011	A 20050311
			JP 2006-43517	A 20060221
			WO 2006-JP304239	W 20060306

OTHER SOURCE(S): MARPAT 145:345245
 ED Entered STN: 14 Sep 2006
 GI

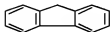


AB The invention relates to base-multiplying agents usable in crosslinking epoxy compds. and so on, which can react with a base to generate another base and which permit efficient progress of base multiplication reaction; and base-reactive curable compns. containing the same. The base-multiplying agents are represented by the general formula I: wherein X is hydrogen, substituted alkyl, or unsubstituted alkylene; Y is a substituted or unsubstituted alkyl chain; and n is an integer of 1 to 4.

IT 86-73-7, Fluorene
 (base multiplying agents)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 23

IT Photoresists
 (base multiplying agents and base-reactive curable compns.)

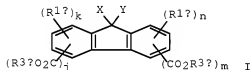
IT 50-00-0, Formaldehyde, reactions 86-73-7, Fluorene
 10193-96-1 10193-99-4 13641-96-8, 2-Isocyanatoethyl acrylate
 15646-96-5 16938-22-0, 2,2,4-Trimethylhexane 1,6-diisocyanate
 (base multiplying agents)

REFERENCE COUNT: 3 THERE ARE 3 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L40 ANSWER 10 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 2006:564344 HCAPLUS [Full-text](#)
 DOCUMENT NUMBER: 145:53326
 TITLE: Preparation of fluorenepolycarboxylic acid esters, photosensitive resin compositions containing them, and pattern formation using it
 INVENTOR(S): Murase, Hiroaki; Ogata, Kazuyuki; Miyauchi, Shinsuke; Kawasaki, Shinichi; Motokawa, Takuya
 PATENT ASSIGNEE(S): Osaka Gas Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokyo Koho, 30 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2006151833	A	20060615	JP 2004-341295	20041125
PRIORITY APPLN. INFO.:			JP 2004-341295	20041125

OTHER SOURCE(S): MARPAT 145:53326
 ED Entered STN: 15 Jun 2006
 GI

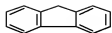


AB The fluorene derivs. I [X = R2aCO2R3c; Y = R2bCO2R3d; R1a, R1b = substituent; R2a, R2b = hydrocarbylene, CH[(R5)pCO2R3e]CHR4 [R4 = H, hydrocarbyl; R5 = (un)substituted hydrocarbylene; p = 0, 1; R3e = H, carboxy-protecting group]; R3a-R3d = H, carboxy-protecting group; k, j, m, n = 0-4; j + k ≤ 4; m + n ≤ 4; if j = m = 0, then R2a and/or R2b = CH[(R5)pCO2R3e]CHR4] (II) are prepared by reacting I (X, Y = H; R1a, R1b, j, k, m, n = same as above; R3a, R3b = carboxy-protecting group) with R6CO2R3 [R6 = R2X [R2 = (un)substituted hydrocarbylene; X = halo], CR7:CHR8 [R7, R8 = H, hydrocarbyl, (R5)pCO2R3 (R3, R5, p = same as above); R7 and/or R8 = H, hydrocarbyl]] in the presence of basic catalysts. The resin compns. contain II, base resins, and photosensitive agents. Addition of II, e.g. 9,9-bis(di-tert-Bu succinate)fluorene, improves sensitivity to and resolution of pos. photoresist.

IT 96-73-7, Fluorene
 (preparation of fluorenepolycarboxylic acid esters and photosensitive resin compns. containing them to improve sensitivity and resolution)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 25
 IT Photoresists
 (preparation of fluorenepolycarboxylic acid esters and photosensitive resin compns. containing them to improve sensitivity and resolution)
 IT 86-73-7, Fluorene 1663-39-4, tert-Butyl acrylate
 18305-60-7, Di-tert-butyl maleate 890135-66-7
 (preparation of fluorenepolycarboxylic acid esters and photosensitive resin compns. containing them to improve sensitivity and resolution)

L40 ANSWER 11 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER:

2006:77306 HCAPLUS [Full-text](#)

DOCUMENT NUMBER:

144:180783

TITLE:

Oxime derivatives and the use thereof as latent acids

INVENTOR(S):

Yamato, Hitoshi; Asakura, Toshikage; Hintermann, Tobias

PATENT ASSIGNEE(S):

Ciba Specialty Chemicals Holding Inc., Switz.

SOURCE:

PCT Int. Appl., 81 pp.

CODEN: PIXXD2

DOCUMENT TYPE:

Patent

LANGUAGE:

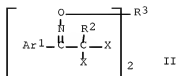
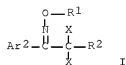
English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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WO 2006008250	A2	20060126	WO 2005-EP53296	20050711
WO 2006008250	A3	20060413		
W:	AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG, BR, BW, BY, BZ, CA, CH, CN, CO, CR, CU, CZ, DE, DK, DM, DZ, EC, EE, EG, ES, FI, GB, GD, GE, GH, GM, HR, HU, ID, IL, IN, IS, JP, KE, KG, KM, KP, KR, KZ, LC, LK, LR, LS, LT, LU, LV, MA, MD, MG, MK, MN, MW, MX, MZ, NA, NG, NI, NO, NZ, OM, PG, PH, PL, PT, RO, RU, SC, SD, SE, SG, SK, SL, SM, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US, UZ, VC, VN, YU, ZA, ZM, ZW			
RW:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR, BF, BJ, CF, CG, CI, CM, GA, GN, GO, GW, ML, MR, NE, SN, TD, TG, BW, GH, GM, KE, LS, MW, MZ, NA, SD, SL, SZ, TZ, UG, ZM, ZW, AM, AZ, BY, KG, KZ, MD, RU, TJ, TM			
CA 2574054	A1	20060126	CA 2005-2574054	20050711
EP 1769286	A2	20070404	EP 2005-774169	20050711
R:	AT, BE, BG, CH, CY, CZ, DE, DK, EE, ES, FI, FR, GB, GR, HU, IE, IS, IT, LI, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR			
CN 1989455	A	20070627	CN 2005-80024529	20050711
JP 2008506749	T	20080306	JP 2007-521939	20050711
US 20080085458	A1	20080410	US 2007-632687	20070117
IN 2007CN00237	A	20070824	IN 2007-CN237	20070119
KR 2007034115	A	20070327	KR 2007-703721	20070215
PRIORITY APPLN. INFO.:			EP 2004-103453	A 20040720

OTHER SOURCE(S): MARPAT 144:180783
 ED Entered STN: 27 Jan 2006
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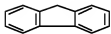


AB The invention pertains to novel photoacid generator compounds. Ar1C(:NOR1)CR2X2, I or II [R1 = C1-C18-alkylsulfonyl or phenylsulfonyl, phenyl-C1-3-alkylsulfonyl, naphthylsulfonyl, anthracylsulfonyl or phenanthrylsulfonyl etc.; R3 = phenylenedisulfonyl, naphthylenedisulfonyl, diphenylenedisulfonyl, or oxydiphenylenedisulfonyl etc.; R2 is halogen or C1-10-haloalkyl; X is halogen; Ar1 = biphenyl or fluorenyl, or is substituted naphthyl etc.; Ar2 = heteroarylene, optionally substituted]. The photoacid generator can be used in pos. photoresist.

IT 86-73-7, Fluorene
 (oxime derivs. and the use thereof as latent acids)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 67

ST oxime deriv photoacid generator pos photoresist

IT Positive photoresists
 (oxime derivs. and the use thereof as latent acids)

IT 86-73-7, Fluorene 92-94-4, p-Terphenyl 98-59-9,
 p-Toluenesulfonyl chloride 5470-11-1, Hydroxyammonium chloride
 41405-35-0
 (oxime derivs. and the use thereof as latent acids)

L40 ANSWER 12 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2005:960139 HCAPLUS Full-text

DOCUMENT NUMBER: 143:275607

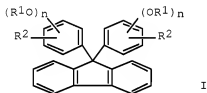
TITLE: 9,9-diphenylfluorenes, and photosensitizers
 containing them, and photoresists
 showing good visible light transparency

INVENTOR(S): Murase, Hiroaki; Sakamoto, Hironori; Yamada,
 Mitsuaki; Morita, Takayuki; Kitano, Satoshi;
 Hosomi, Tetsuya

PATENT ASSIGNEE(S): Osaka Gas Co., Ltd., Japan; Nagase Chemtex Corp.
 SOURCE: Jpn. Kokai Tokkyo Koho, 20 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2005232112	A	20050902	JP 2004-45541	20040223
KR 2006043055	A	20060515	KR 2005-14427	20050222
PRIORITY APPLN. INFO.:			JP 2004-45541	A 20040223

OTHER SOURCE(S): MARPAT 143:275607
 ED Entered STN: 02 Sep 2005
 GI

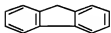


AB The diphenylfluorenes are I (R1 = H, quinonediazidosulfonyl; ≥1 of R1 = quinonediazidosulfonyl; R2 = H, C1-6 alkyl; n = 2, 3). The photoresists, preferably pos.-working, contain alkali-soluble resins and photosensitizers containing I produce images showing good heat and chemical resistance.

IT 86-73-7, Fluorene
 (diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



IC ICM C07C309-76
 ICS C08K005-41; C08L101-00; G03F007-022; G03F007-038; H01L021-027

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 25, 38

ST quinonediazidosulfonyloxy diphenylfluorene photosensitizer pos photoresist

IT Positive photoresists
 (diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)

IT Aminoplasts

- Epoxy resins, uses
(diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)
- IT Phenolic resins, uses
(novolak; diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)
- IT Catalysts
(photochem.; diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)
- IT 863658-55-3P 863658-56-4P
(diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)
- IT 351521-78-3P, 9,9-Bis(3',4'-dihydroxyphenyl)fluorene 848873-54-1P
(diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)
- IT 86-73-7, Fluorene 87-66-1, Pyrogallol 120-80-9, Catechol, reactions 3770-97-6, 1,2-Naphthoquinonediazido-5-sulfonyl chloride
(diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)
- IT 9003-08-1, Nikalac MW 100LM 58141-48-3,
o-Cresol-m-cresol-formaldehyde copolymer 125370-98-1, Techmore VG 3101
(diphenylfluorenes bearing quinonediazidosulfonyloxy groups as photosensitizers for pos.-working photoresists)

L40 ANSWER 13 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 2004:117761 HCAPLUS Full-text

DOCUMENT NUMBER: 140:171933

TITLE: Polycyclic aromatic hydrocarbons as
electroluminescent substances for organic
electroluminescent devices

INVENTOR(S): Ishida, Tsutomu; Shimamura, Takehiko; Tanabe,
Yoshimitsu; Totani, Yoshiyuki; Nakatsuka,
Masakatsu

PATENT ASSIGNEE(S): Mitsui Chemicals Inc., Japan
SOURCE: Jpn. Kokai Tokkyo Koho, 81 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent
LANGUAGE: Japanese

FAMILY ACC. NUM. COUNT: 1

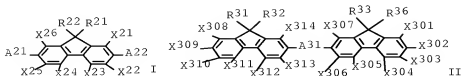
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 2004043349	A	20040212	JP 2002-202163	20020711
PRIORITY APPLN. INFO.:			JP 2002-202163	20020711

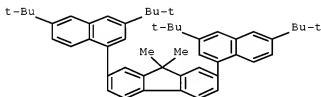
OTHER SOURCE(S): MARPAT 140:171933

ED Entered STN: 13 Feb 2004

GI



- AB The hydrocarbons, having direct linkages between fluorenes and polycyclic aromatic groups other than anthracenes, are X1F1jA1kF21A2mF3nX2, I, or II (A1, A2, A21, A22, A31 = divalent polycyclic aromatic group; F1-F3 = fluorenediyl; R21, R22, R31-R34 = H, alkyl, aryl, aralkyl; X1, X2, X21-X26, X301-X314 = H, halo, linear or branched alkyl, cycloalkyl, etc.; A1, A2, A31 ≠ anthracenediyl; X1, X2, A21, A22 ≠ anthryl; X21-X26, X301-X314, R21, R22, R31-R34 ≠ fluorenyl, polycyclic aromatic group; j, m, n = 0, 1; k, l = 1, 2). The devices having emitter layers containing the hydrocarbons as hosts or dopants show high luminescence efficiency and long service life.
- IT 654664-47-8P
(hydrocarbons having direct linkages between fluorenes and polycyclic aromatic groups as hosts or dopants for emitter layers in organic electroluminescent devices)
- RN 654664-47-8 HCAPLUS
- CN 9H-Fluorene, 2,7-bis[3,6-bis(1,1-dimethylethyl)-1-naphthalenyl]-9,9-dimethyl- (CA INDEX NAME)



- IC ICM C07C013-547
ICS C07C013-62; C07C013-66; C07C211-57; C07C211-61; C09K011-06;
H05B033-14
- CC 73-11 (Optical, Electron, and Mass Spectroscopy and Other Related Properties)
Section cross-reference(s): 25
- IT 653590-49-9P 653590-65-9P 653590-82-0P 653599-36-1P
653599-38-3P 653599-45-2P 653599-55-4P 654664-36-5P
654664-37-6P 654664-38-7P 654664-39-8P 654664-40-1P
654664-41-2P 654664-43-4P 654664-44-5P 654664-45-6P
654664-46-7P 654664-47-8P 654664-48-9P 654664-49-0P
654664-50-3P 654664-51-4P 654664-52-5P 654664-53-6P
654664-54-7P 654664-55-8P 654664-56-9P 654664-57-0P
654664-58-1P 654664-59-2P 654664-60-5P 654664-61-6P
654664-62-7P
(hydrocarbons having direct linkages between fluorenes and polycyclic aromatic groups as hosts or dopants for emitter layers in organic electroluminescent devices)
- L40 ANSWER 14 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
- ACCESSION NUMBER: 2004:117590 HCAPLUS [Full-text](#)
- DOCUMENT NUMBER: 140:154552
- TITLE: Optical recording medium for blue light-emitting semiconductor laser
- INVENTOR(S): Ishida, Tsutomu; Saito, Yasunori; Shiozaki, Hiroyuki; Ogiso, Akira; Tsukahara, Hiroshi; Shimamura, Takehiko; Tanabe, Yoshimitsu; Totani, Yoshiyuki; Nakatsuka, Masakatsu
- PATENT ASSIGNEE(S): Mitsui Chemicals Inc., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 81 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 2004042485	A	20040212	JP 2002-204170	20020712
PRIORITY APPLN. INFO.:			JP 2002-204170	20020712

OTHER SOURCE(S): MARPAT 140:154552

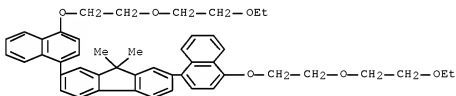
ED Entered STN: 13 Feb 2004

AB The recording medium has ≥ 1 layer containing ≥ 1 hydrocarbon directly linked with fluorenes and condensed polycyclic aromatic ring. The medium is capable of recording and regenerating of information under 300-500 nm laser, e.g., blue-violet GaN laser diode. The hydrocarbons themselves are also claimed.

IT 653599-39-4 653599-49-6 653599-57-6
 (optical recording medium containing fluorene-linked condensed polycyclic aromatic hydrocarbon for blue semiconductor laser)

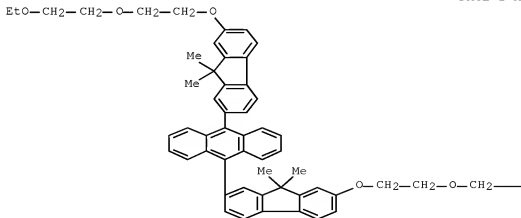
RN 653599-39-4 HCAPLUS

CN 9H-Fluorene, 2,7-bis[4-[2-(2-ethoxyethoxy)ethoxy]-1-naphthalenyl]-9,9-dimethyl- (CA INDEX NAME)



RN 653599-49-6 HCAPLUS

CN Anthracene, 9,10-bis[7-[2-(2-ethoxyethoxy)ethoxy]-9,9-dimethyl-9H-fluoren-2-yl]- (CA INDEX NAME)



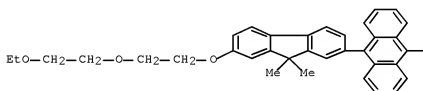
PAGE 1-A

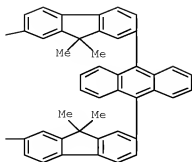
PAGE 1-B

—CH₂—OEt

RN 653599-57-6 HCAPLUS
 CN Anthracene, 9,9'-(9,9-dimethyl-9H-fluorene-2,7-diyl)bis[10-[7-[2-(2-ethoxyethoxy)ethoxy]ethoxy]-9,9-dimethyl-9H-fluoren-2-yl]- (CA INDEX NAME)

PAGE 1-A

EtO—CH₂—CH₂—O—CH₂—CH₂—O



IC ICM B41M005-26
ICS G11B007-004; G11B007-24
CC 74-12 (Radiation Chemistry, Photochemistry, and Photographic
and Other Reprographic Processes)
Section cross-reference(s): 73, 76
IT 400605-76-7 400605-92-7 400606-62-4 400606-81-7 400606-82-8
400606-84-0 400606-91-9 626236-30-4 653590-49-9 653590-65-9
653590-67-1 653590-82-0 653590-83-1 653591-68-5 653599-36-1
653599-37-2 653599-38-3 653599-39-4 653599-40-7
653599-41-8 653599-42-9 653599-43-0 653599-44-1 653599-45-2
653599-46-3 653599-47-4 653599-48-5 653599-49-6
653599-50-9 653599-51-0 653599-52-1 653599-53-2 653599-54-3
653599-55-4 653599-56-5 653599-57-6 653599-58-7
653600-44-3 653600-45-4 653600-46-5 653600-49-8
(optical recording medium containing fluorene-linked condensed
polycyclic aromatic hydrocarbon for blue semiconductor laser)

L40 ANSWER 15 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 2001:449940 HCAPLUS [Full-text](#)
DOCUMENT NUMBER: 135:38968
TITLE: Microlens formed of negative photoresist
INVENTOR(S): Li, Zong-fu
PATENT ASSIGNEE(S): Intel Corporation, USA
SOURCE: U.S., 6 pp.
CODEN: USXXAM
DOCUMENT TYPE: Patent
LANGUAGE: English
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

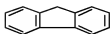
PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
US 6249034	B1	20010619	US 1999-280434	19990329
US 6509140	B1	20030121	US 2000-709873	20001110
US 20030054295	A1	20030320	US 2002-284929	20021031
US 6646808	B2	20031111		
PRIORITY APPLN. INFO.:			US 1999-280434	A3 19990329
			US 2000-709873	A3 20001110

ED Entered STN: 21 Jun 2001

AB An imaging array is described which comprises a photosensitive element with a passivation layer over it, a microlens over the layer, and a scratch

protection layer formed of neg. photoresist over the passivation layer in areas where there are no microlenses. Neg. photoresists with high thermal stability and high transparency, particularly, epoxy acrylates having the fluorene moiety, have desirable characteristics.

IT 86-73-7D, Fluorene, derivs., polymers
 (imaging array containing microlens formed of neg. photoresist
)
 RN 86-73-7 HCAPLUS
 CN 9H-Fluorene (CA INDEX NAME)



IC ICM H01L031-0232
 INCL 257432000
 CC 74-13 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 Section cross-reference(s): 42, 73
 ST imaging array microlens neg photoresist; epoxy acrylate
 fluorene neg photoresist imaging array microlens
 IT Epoxy resins, processes
 (acrylates; imaging array containing microlens formed of neg.
 photoresist)
 IT Optical imaging devices
 (arrays; imaging array containing microlens formed of neg.
 photoresist)
 IT Microlenses
 Negative photoresists
 (imaging array containing microlens formed of neg. photoresist
)
 IT 86-73-7D, Fluorene, derivs., polymers
 (imaging array containing microlens formed of neg. photoresist
)
 REFERENCE COUNT: 2 THERE ARE 2 CITED REFERENCES AVAILABLE FOR
 THIS RECORD. ALL CITATIONS AVAILABLE IN THE
 RE FORMAT

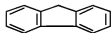
L40 ANSWER 16 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 1999:271577 HCAPLUS Full-text
 DOCUMENT NUMBER: 130:289209
 TITLE: Polyimide composition for positive
 photoresist
 INVENTOR(S): Itatani, Hiroshi; Matsumoto, Shunichi
 PATENT ASSIGNEE(S): PI R & D Co., Ltd., Japan
 SOURCE: PCT Int. Appl., 112 pp.
 CODEN: PIXXD2
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 2
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
WO 9919771	A1	19990422	WO 1998-JP4577	19981012
W: CN, JP, KR, US				

RW: AT, BE, CH, CY, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC,
 NL, PT, SE
 EP 1024407 A1 20000802 EP 1998-947813 19981012
 R: AT, BE, CH, DE, DK, ES, FR, GB, GR, IT, LI, LU, NL, SE, MC,
 PT, IE, FI
 US 6627377 B1 20030930 US 2000-529382 20000626
 JP 1997-315781 A 19971013
 JP 1997-320266 A 19971016
 JP 1997-353987 A 19971117
 JP 1997-353988 A 19971117
 JP 1997-363044 A 19971125
 JP 1997-363045 A 19971125
 JP 1997-363378 A 19971126
 JP 1997-365491 A 19971202
 JP 1997-370187 A 19971222
 JP 1998-31933 A 19980105
 JP 1998-108410 A 19980316
 JP 1997-352987 A 19971117
 WO 1998-JP4577 W 19981012

PRIORITY APPLN. INFO.:

ED Entered STN: 03 May 1999
 AB A photosensitive polyimide composition is soluble in organic solvents, excellent in adhesiveness, heat resistance, mech. characteristics and flexibility, and is capable of exhibiting alkali-soluble, highly sensitive pos. photoresist characteristics upon irradiation with light. The composition comprises a photo-acid generator and a solvent soluble polyimide exhibiting pos. photosensitivity in the presence of the generator.
 IT 86-73-7, Fluorene
 (polyimide composition for pos. photoresist)
 RN 86-73-7 HCAPLUS
 CN 9H-Fluorene (CA INDEX NAME)



IC ICM G03F007-039
 ICS G03F007-022; G03F007-004; C08L079-08; C09D179-08; C08G073-10;
 H05K003-28; H05K003-46; H01L021-027
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic
 and Other Reprographic Processes)
 Section cross-reference(s): 35
 ST polyimide compn pos photoresist
 IT Positive photoresists

- (polyimide composition for pos. photoresist)
- IT Polyimides, uses
(polyimide composition for pos. photoresist)
- IT 15499-84-0P
(polyimide composition for pos. photoresist)
- IT 80180-96-7P, 3,3',4,4'-Benzophenonetetracarboxylic dianhydride-2,4-diaminotoluene-3,3'-dimethoxy-4,4'-diaminobiphenyl copolymer 87182-96-5P, 2,2-Bis[4-(4-aminophenoxy)phenyl]hexafluoropropane-4,4'-[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]bis(1,2-benzenedicarboxylic acid dianhydride) copolymer 134096-63-2P 144279-09-4P 162735-41-3P 177190-29-3P 177190-34-0P 186967-17-9P 222842-97-9P, 3,4,3',4'-Biphenyltetracarboxylic acid dianhydride-2,2-bis[4-(4-aminophenoxy)phenyl]propane-2,3-diaminodiphenyl ether copolymer 222843-01-8P 222843-06-3P, 3,4,3',4'-Biphenyltetracarboxylic acid dianhydride-3,4,3',4'-benzophenonetetracarboxylic acid dianhydride-2,4-diaminotoluene-diaminosiloxane-3,4-diaminodiphenyl ether-2,2-bis[4-(4-aminophenoxy)phenyl]hexafluoropropane block copolymer 222843-27-8P, m-BAPS-3,4,3',4'-benzophenonetetracarboxylic acid dianhydride-9,9-bis(4-aminophenyl)fluorene-3,4,3',4'-Biphenyltetracarboxylic acid dianhydride-3,5-diaminobenzoic acid block copolymer 222843-32-5P 222843-36-9P, 3,4,3',4'-Benzophenonetetracarboxylic Acid Dianhydride-4,4'-diaminodiphenylsulfide-3,4,3',4'-biphenyl tetracarboxylic Acid Dianhydride-3,3'-dihydroxybenzidine-m-BAPS block copolymer 222843-50-7P 222843-56-3P 222843-63-2P 222843-70-1P 222843-77-8P 222843-82-5P 222843-88-1P 222843-94-9P 222843-98-3P 222844-05-5P 222844-10-2P 222844-17-9P 222844-25-9P 222844-32-8P 222844-44-2P 222844-51-1P 222844-59-9P 222844-67-9P 222844-73-7P, 3,3',4,4'-Biphenyltetracarboxylic dianhydride; diaminosilane; γ -valerolactone; 3,4,3',4'-benzophenonetetracarboxylic dianhydride; 3,3'-dihydroxy-4,4'-diaminobiphenyl; 3,4'-diaminodiphenyl ether block copolymer 222844-82-8P 222844-87-3P 222844-93-1P 222844-96-4P 222845-03-6P 222845-07-0P, 3,3',4,4'-Benzophenonetetracarboxylic acid dianhydride-3,3'-dinitro-4,4'-diaminodiphenyl-bis[4-(3-Aminophenyl)phenyl]sulfone copolymer 222845-11-6P 222845-17-2P 222845-23-0P 222845-26-3P 222845-32-1P 222845-38-7P, 3,3',4,4'-Biphenyltetracarboxylic acid anhydride-1,5-diaminoanthraquinone-2,2-bis[4-(3-aminophenoxy)phenyl]propane copolymer 222845-43-4P 222845-53-6P 222845-58-1P 222845-63-8P 222845-68-3P, 3,3',4,4'-Benzophenonetetracarboxylic acid dianhydride-1,4-bis(3-aminopropyl)piperazine-bis[4-(3-aminophenoxy)phenyl]sulfone copolymer 222845-73-0P 222845-77-4P 222845-83-2P 222845-89-8P 222845-95-6P 222846-01-7P 222846-08-4P 222846-13-1P 222846-18-6P 222846-23-3P, 3,3',4,4'-Biphenyltetracarboxylic acid dianhydride-bis-4-(3-aminophenoxy)phenylsulfone-2,2-bis-[4-(3-aminophenoxy)phenyl]hexafluoropropane copolymer 222846-30-2P 222846-54-0P 222846-63-1P 222846-79-9P 222846-83-5P 222846-88-0P, 3,4,3',4'-Biphenyltetracarboxylic acid dianhydride-2,2-ditrifluoromethylbenzidine-2,2-bis[4-(4-aminophenoxy)phenyl]propane-3,5-diaminobenzoic acid block copolymer 222846-93-7P
(polyimide composition for pos. photoresist)
- IT 86-73-7, Fluorene
(polyimide composition for pos. photoresist)

IT 83803-86-5 222843-16-5, m-BAPS-3,3'-dimethylbenzidine-4,4'-[2,2,2-trifluoro-1-(trifluoromethyl)ethylidene]bis(1,2-benzenedicarboxylic acid dianhydride) copolymer 222843-21-2, m-BAPS-bicyclo(2,2,2)-octa-7-ene-2,3,5,6-tetracarboxylic acid dianhydride-pyromellitic acid dianhydride copolymer 222843-41-6, 2,2-Bis[4-(4-aminophenoxy)phenyl]propane-3,4,3',4'-Biphenyltetracarboxylic dianhydride-3,5-diaminobenzoic acid-pyromellitic acid dianhydride-2,2'-bis(trifluoromethyl) benzidine block copolymer
(polyimide composition for pos. photoresist)

REFERENCE COUNT: 13 THERE ARE 13 CITED REFERENCES AVAILABLE FOR THIS RECORD. ALL CITATIONS AVAILABLE IN THE RE FORMAT

L40 ANSWER 17 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 1997:553940 HCAPLUS Full-text

DOCUMENT NUMBER: 127:227437

ORIGINAL REFERENCE NO.: 127:44223a,44226a

TITLE: Polymer and resist material

INVENTOR(S): Urano, Fumiyoshi; Fujie, Hirotoishi; Oono, Keiji

PATENT ASSIGNEE(S): Wako Pure Chemical Industries, Ltd., Japan

SOURCE: Eur. Pat. Appl., 46 pp.

CODEN: EPXXDW

DOCUMENT TYPE: Patent

LANGUAGE: English

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
EP 789279	A1	19970813	EP 1996-309141	19961213
EP 789279	B1	20010321		
EP 789279	B2	20041208		
R: AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LI, LU, MC, NL, PT, SE				
AT 199985	T	20010415	AT 1996-309141	19961213
US 6033826	A	20000307	US 1996-769530	19961219
CN 1159453	A	19970917	CN 1996-123157	19961220
CN 1145078	C	20040407		
TW 440744	B	20010616	TW 1996-85115781	19961220
JP 10053621	A	19980224	JP 1997-35572	19970204
JP 3724098	B2	20051207		

PRIORITY APPLN. INFO.: JP 1996-47955 A 19960209

JP 1996-168387 A 19960607

OTHER SOURCE(S): MARPAT 127:227437

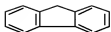
ED Entered STN: 30 Aug 1997

AB A copolymer of hydroxystyrene containing an acetal or ketal group which can easily be eliminated in the presence of an acid in the mol. and having a very narrow mol. weight distribution gives a resist material suitable for forming ultrafine patterns excellent in resolution, heat resistance, mask linearity, and other properties without causing problems of delay time and the like.

IT 96-73-7B, Fluorene, azo derivs
(resist materials containing hydroxystyrene copolymer containing acetal or ketal groups and)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



IC ICM G03F007-039
 ICS G03F007-004; C08F212-14; C08F012-14; C08F112-14
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
 ST photoresist hydroxystyrene copolymer acetal group
 IT Photoresists
 (hydroxystyrene copolymers containing acetal or ketal groups for)
 IT 69-72-7, Salicylic acid, uses 86-73-7D, Fluorene, azo derivs
 89-73-6, Salicylhydroxamic acid 131-55-5,
 2,2',4,4'-Tetrahydroxybenzophenone 577-56-0, o-Acetylbenzoic acid
 758-96-3, N,N-Dimethylpropionamide 832-80-4, 9-Diazofluorene
 1116-76-3, Trioctylamine 1886-74-4 2321-07-5, Fluorescein
 4387-82-0, N,N-Dimethylolacetamide 7509-44-6,
 9-Diazo-10-phenanthrone 9004-95-9, Polyoxyethylene cetyl ether
 14159-45-6 28322-50-1 66003-78-9, Triphenylsulfonium
 trifluoromethanesulfonate 138529-81-4,
 Bis(cyclohexylsulfonyl)diazomethane 138529-83-6 138529-84-7
 138529-91-6 171429-57-5 177034-79-6 194996-92-4
 (resist materials containing hydroxystyrene copolymer containing acetal or ketal groups and)

L40 ANSWER 18 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 1991:682049 HCAPLUS Full-text

DOCUMENT NUMBER: 115:282049

ORIGINAL REFERENCE NO.: 115:47913a, 47916a

TITLE: Polycyclic aromatic organosilica gels and azo dyes based on them

AUTHOR(S): Mkheidze, N. P.; Apkhazava, P. N.; Chirakadze, G. G.

CORPORATE SOURCE: Gruz. Tekh. Inst., Tbilisi, USSR

SOURCE: Izvestiya Akademii Nauk Gruzinskoi SSR, Seriya Khimicheskaya (1990), 16(2), 98-103
 CODEN: IGSKDH; ISSN: 0132-6074

DOCUMENT TYPE: Journal

LANGUAGE: Russian

OTHER SOURCE(S): CASREACT 115:282049

ED Entered STN: 27 Dec 1991

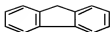
AB New organosilica gels, containing fragments of fluorene (I) and fluoranthene (II) chemical bonded with atoms of silicon of the inorg. matrix, were synthesized. Consecutive reactions were conducted on the gels to give diazo components. New azo dyes were synthesized by coupling of β -naphthol, H-acid, indole, m-aminophenol, fluorescein and naphthionic acid with the diazo components. The obtained azo dyes were characterized by color variety, light resistance, and fastness to wet treatment. The quantity of immobilized fragments on the surface of silica gel was equal to 5.11 (I) and 1.73% (II). The structure of the grafted azo dyes was confirmed by UV spectra.

IT 86-73-7, Fluorene

(nitration of)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



CC 41-3 (Dyes, Organic Pigments, Fluorescent Brighteners, and
Photographic Sensitizers)
IT 86-73-7, Fluorene 206-44-0, Fluoranthene
(nitration of)

L40 ANSWER 19 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
ACCESSION NUMBER: 1989:544117 HCAPLUS Full-text
DOCUMENT NUMBER: 111:144117
ORIGINAL REFERENCE NO.: 111:23909a,23912a
TITLE: Heat-resistant photosensitive polymer compositions
INVENTOR(S): Kataoka, Fumio; Shoji, Fusaji; Tanaka, Jun;
Yamazaki, Tetsuya; Kojima, Mitumasa
PATENT ASSIGNEE(S): Hitachi, Ltd., Japan; Hitachi Chemical Co., Ltd.
SOURCE: Jpn. Kokai Tokkyo Koho, 12 pp.
CODEN: JKXXAF
DOCUMENT TYPE: Patent
LANGUAGE: Japanese
FAMILY ACC. NUM. COUNT: 1
PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
JP 63318549	A	19881227	JP 1987-154757	19870622
JP 06046302	B	19940615		

PRIORITY APPLN. INFO.: JP 1987-154757 19870622

ED Entered STN: 14 Oct 1989

AB The neg.-working title compns. contain 100 parts of a polymer of the repeating unit -COR1(CO2R3)(CO2R4)CONHR2(XY)nNH- (R1 = C24 tetravalent organic group; R2 = a tri- or tetravalent organic group containing an aromatic ring; R3, R4 = C≤10 organic group; Y = a photosensitive group; X = an organic group, O, NH; n = 1, 2) and 0.1-30 parts of a photopolymer. initiator, photocrosslinker, and/or photosensitizer.

IT 86-73-7, 9H-Fluorene
(photoresists containing, heat-resistant)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



IC ICM G03C001-71

ICS C08G073-10

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic
and Other Reprographic Processes)

ST polyamic acid neg working photoresist; photocrosslinker neg
working photoresist; photoinitiator neg working

photoresist; photosensitizer neg working photoresist
 ; polyimide neg working photoresist

IT Polyamic acids
 (photoresists containing, heat-resistant)

IT Heat-resistant materials
 (polyamic acid photoresists)

IT Crosslinking catalysts
 (photochem., for polyamic acid photoresists)

IT 66-77-3, 1-Naphthaldehyde 68-11-1, uses and miscellaneous 79-42-5
 82-05-3, 7H-Benz[de]anthracene-7-one 86-73-7, 9H-Fluorene
 86-93-1 90-44-8, Anthrone 90-93-7,
 Bis-4,4'-diethylaminobenzophenone 90-94-8, Michler's ketone
 119-61-9, Benzophenone, uses and miscellaneous 126-58-9,
 Dipentaerythritol 260-94-6, Acridine 492-22-8,
 9H-Thioxanthene-9-one 574-09-4, Benzoil ethyl ether 602-87-9,
 5-Nitroacenaphthene 607-57-8, 2-Nitrofluorene 641-13-4,
 Dibenzo[def,mno]chrysene-6,12-dione 703-80-0 1785-51-9,
 Pyrene-1,6-quinone 2498-66-0, 1,2-Benzoanthraquinone 3508-73-4
 5284-79-7 5960-69-0 6652-28-4 7575-23-7, Pentaerythritol
 tetra(3-mercaptopropionate) 10193-98-3 10193-99-4, Pentaerythritol
 tetrathiolglycolate 10287-54-4 10312-58-0, Trimethylolethane
 tris(3-mercaptopropionate) 20237-98-3,
 2,6-Bis(4-azidobenzal)cyclohexanone 21245-01-2 22504-50-3,
 Ethylene glycol bis(3-mercaptopropionate) 33007-83-9,
 Trimethylolpropane tris(3-mercaptopropionate) 35210-50-5
 35460-17-4 37265-25-1, Ethylene glycol thioglycolate 42397-65-9,
 1,8-Dinitropyrene 42759-78-4 42759-79-5 49600-94-4 49600-95-5
 63021-86-3, Nitropyrene 80208-77-1, Trimethylolpropane thioglycolate
 85179-71-1 86776-28-5 91528-47-1, Ethyl dimethylaminobenzoate
 95543-55-8 122638-13-5 122638-14-6 122638-15-7 122638-16-8
 122644-00-2 122644-02-4 122644-03-5 122644-05-7 122644-54-6
 122644-55-7 122644-56-8 122659-00-1 122659-01-2 122659-42-1
 122681-83-8 122694-43-3 122727-61-1
 (photoresists containing, heat-resistant)

L40 ANSWER 20 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 1988:519706 HCAPLUS Full-text

DOCUMENT NUMBER: 109:119706

ORIGINAL REFERENCE NO.: 109:19789a,19792a

TITLE: Photohardenable layer material, method for its
 production, and printed circuit production
 therefrom

INVENTOR(S): Nakazaki, Nobuo; Ai, Hideo; Miyao, Manabu

PATENT ASSIGNEE(S): Asahi Chemical Industry Co., Ltd., Japan

SOURCE: Ger. Offen., 28 pp.

CODEN: GWXXBX

DOCUMENT TYPE: Patent

LANGUAGE: German

FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 3732801	A1	19880407	DE 1987-3732801	19870929
DE 3732801	C2	19930304		
JP 63085538	A	19880416	JP 1986-231058	19860929
JP 01013138	A	19890118	JP 1987-169507	19870707
JP 01014262	A	19890118	JP 1987-169508	19870707
US 4839261	A	19890613	US 1987-96479	19870915
GB 2196639	A	19880505	GB 1987-21966	19870918

10/531,208

GB 2196639	B	19900725		
FR 2604534	A1	19880401	FR 1987-13384	19870928
FR 2604534	B1	19911018		

PRIORITY APPLN. INFO.:

	JP 1986-231058	A	19860929
	JP 1987-169507	A	19870707
	JP 1987-169508	A	19870707

ED Entered STN: 01 Oct 1988
GI

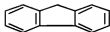


AB A photohardenable layer material, which can be used for the production of printed circuits on printing plates, consists of a transparent support and a photohardenable layer containing 100 parts of a compound with repeating units of the formula I (R = vinyl, epoxy, or episulfide group; R1 = H, C1-6 alkyl, or halogen; and R and R1 are in the ortho, meta, or para position to the C atom of the main chain) and CWXCYZ [W, X, Y, and Z = H, halogen, CN, (un)substituted alkyl or aryl, (un)substituted ether or ester, NO2, Si-containing-group, or a heterocyclic ring-substituted group], and 5-1000 parts of a compound that is compatible with the above-mentioned compound and has a double bond-containing group and a viscosity of 0.0001-50 Pa-s at 20°. A mixture containing Aronix M-305, epoxidized p-divinylbenzene-2-vinylnaphthalene copolymer, benzophenone, Michler's ketones, and MEK was prepared was coated on a PET film, dried, pressed upon the Cu surface of a Cu-clad glass fiber-epoxy resin laminate, imagewise exposed, the PET film stripped off, and the image developed with 1,1,1-trichloroethane to give a good image.

IT 86-73-7, Fluorene
(dry-film photoresists containing)

RN 86-73-7 HCAPLUS

CN 9H-Fluorene (CA INDEX NAME)



IC ICM G03F007-10
ICS G03C001-72; H01L021-312; C08F002-48; B32B015-08; B32B027-06

ICA H05K003-00; C08J003-28; C08J003-24

CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)

ST dry film photoimaging material; photoresist dry film; printing plate dry film photoimaging

- IT Electric circuits
(printed, dry-film photoresists for fabrication of)
- IT 96-73-7, Fluorene 90-94-8, Michler's ketone 119-61-9,
Benzophenone, uses and miscellaneous 134-85-0, 4-Chlorobenzophenone
603-35-0, Triphenylphosphine, uses and miscellaneous 3524-68-3
9003-53-6 9003-55-8 9011-14-7 10287-53-3, Ethyl
4-(dimethylamino)benzoate 21908-85-0 24650-42-8 61722-28-9, BP
4PA 68224-34-0, D-330 75980-60-8,
2,4,6-Trimethylbenzoyldiphenylphosphine oxide 95543-55-8,
Isopropyl-4-(dimethylamino)benzoate 95567-09-2, Aronix 8100
95971-30-5, 2,4-Diisopropylthioxanthone 116111-51-4 116134-95-3
116237-19-5
(dry-film photoresists containing)
- IT 62-56-6DP, Thiourea, reaction products with styrene-vinylstyrene oxide
copolymers 26101-54-2DP, reaction products with thiourea
26101-54-2P 103945-31-9P 105430-21-5P 107810-72-0P
107810-73-1P 114975-34-7P 116111-49-0P 116111-50-3P
116111-70-7P 116134-85-1P 116134-90-8P 116134-91-9P
116134-92-0DP, epoxidized 116134-93-1P 116134-94-2P 116134-96-4P
116237-20-8P 116237-21-9P 116266-04-7P
(preparation and dry-film photoresists containing)

L40 ANSWER 21 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 1988:483443 HCAPLUS [Full-text](#)

DOCUMENT NUMBER: 109:83443

ORIGINAL REFERENCE NO.: 109:13783a,13786a

TITLE: Photopolymerizing laminates for printed circuits

INVENTOR(S): Ai, Hideo; Ikeda, Akihiko; Sato, Jiro

PATENT ASSIGNEE(S): Asahi Glass Co., Ltd., Japan

SOURCE: Jpn. Kokai Tokkyo Koho, 17 pp.

CODEN: JKXXAF

DOCUMENT TYPE: Patent

LANGUAGE: Japanese

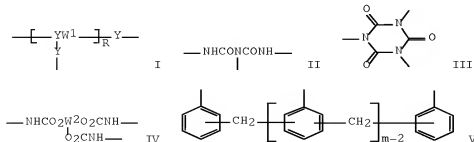
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 61077844	A	19860421	JP 1984-199452	19840926
JP 05050737	B	19930729		
PRIORITY APPLN. INFO.:			JP 1984-199452	19840926

ED Entered STN: 02 Sep 1988

GI



- AB The photopolymerizable resin layer of the title laminate is composed of (1) a vinyl (co)polymer binder 5-95, (2) a photopolymerizable compound selected from $\text{RY}(\text{NHCO}_2\text{ZCONHY})_n\text{R}$, $\text{Rm}\bar{\text{W}}$, and $\text{Rm-1WNHCO}_2\text{ZCONHWRm-1}$ [$\text{R} = \text{CH}_2:\text{CR1CO}_2\text{XCHR2O}_2\text{CNH}$; $n \geq 0$; $m = 3-10$; $\text{R1} = \text{H, Me}$; $\text{X} = \text{C1-8}$ divalent aliphatic hydrocarbon moiety, $(\text{CH}_2\text{CHR3O})_p\text{CH}_2$, $(\text{CH}_2)\text{qO}_2\text{CC6H}_4\text{CO}_2(\text{CH}_2)_r$; $\text{R2} = \text{C1-6}$ alkyl, $\text{CH}_2\text{OR4}$; $\text{R3} = \text{C1-4}$ alkyl; $\text{R4} = \text{Ph, aryl, C1-6 alkyl}$; $\text{Y} = \text{C2-16}$ divalent hydrocarbon moiety; $\text{Z} = (\text{CH}_2)\text{tO}$, $(\text{CH}_2\text{CHR3O})_x$, $\text{CH}_2\text{CMe}_2\text{CH}_2\text{O}$, $\text{CHR5CH}_2\text{OZ1CH}_2\text{CHR5O}$; $\text{R5} = \text{CH}_2:\text{CR1CO}_2\text{CH}_2$; $\text{Z1} = (\text{CH}_2)\text{tO}$, $(\text{CH}_2\text{CHR1O})_x$, $\text{CH}_2\text{CMe}_2\text{CH}_2\text{O}$, $\text{COC6H}_4\text{CO}_2$, $\text{CH}_2\text{CHR1O-p-C6H}_4\text{CMe}_2\text{-p-C6H}_4\text{OCHR1CH}_2\text{O}$; $\text{W} = \text{I}$; $\text{W1} = \text{II, III, IV, V}$; $\text{W2} = \text{trivalent C3-10 hydrocarbon moiety}$; $p = 1-10$; $q, r = 1-4$; $t = 2-10$; $x = 1-30$; $s = 1-5$) 5-95, and (3) a photopolymer. initiator 0.01-30 weight%. The title laminate is especially useful for fabrication of printed circuit boards. Thus, a poly(ethylene terephthalate) film was coated with a photosensitive resin composition containing Bu acrylate-Me methacrylate copolymer, a hexamethylene diisocyanate-2-hydroxypropyl acrylate adduct, benzophenone, Michler's ketone, Dia Resin Blue P, benzotriazole, and p-methoxyphenol, and the film was laminated on a Cu-laminated glass fiber-enforced epoxy resin plate. Imagewise exposure from the film side and subsequent development of the resist layer gave high quality resist pattern on the Cu laminated board.
- IT 86-73-7
(photoresist comps. containing, dry-film type)
- RN 86-73-7 HCAPLUS
- CN 9H-Fluorene (CA INDEX NAME)



- IC ICM G03C001-68
ICS G03C001-00; G03F007-10
- ICA C08F002-48; C08F299-06
- CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 76
- ST photoresist laminate printed circuit board; urethane prepolymer photoresist
- IT Electric circuits
(printed, photoresist laminates for preparation of)
- IT 81-48-1, Dia Resin Blue-G 86-73-7 90-94-8,
4,4'-Bis(dimethylamino)benzophenone 95-14-7, Benzotriazole
101-68-8D, Diphenylmethane diisocyanate, adducts with hydroxypropyl
acrylate 119-61-9, Benzophenone, uses and miscellaneous 134-85-0,
4-Chlorobenzophenone 150-76-5, p-Methoxyphenol 603-35-0,
Triphenylphosphine, uses and miscellaneous 822-06-0D, Hexamethylene
diisocyanate, adducts with hydroxypropyl acrylate 999-61-1D,
2-Hydroxypropyl acrylate, reaction products with diisocyanates
2475-44-7 3524-68-3, Aronix M-305 4098-71-9D, adducts with
hydroxypropyl acrylate 9003-53-6, Styron GP685 9011-14-7, Delpet
70H 10287-53-3, Ethyl 4-dimethylaminobenzoate 16969-10-1D,
2-Hydroxy-3-phenoxypropyl acrylate, adducts with hexamethylene
diisocyanate 21908-85-0 24650-42-8 25322-68-3D, Polyethylene

glycol, adducts with hexamethylene diisocyanate and hydroxypropyl acrylate 25852-37-3, Butyl acrylate-methyl methacrylate copolymer 26471-62-5D, Tolylene diisocyanate, adducts with hydroxypropyl acrylate 37293-38-2D, Coronate HL, adducts with hydroxypropyl acrylate 39278-79-0D, Coronate L, adducts with hydroxypropylacrylate 39420-45-6D, adducts with hexamethylene diisocyanate 60506-81-2 61722-28-9 68224-34-0, D-330 72928-42-8 72928-42-8D, reaction products with tolylene diisocyanate-hydroxypropyl acrylate adduct 74315-89-2, Dia Resin Green-C 81544-19-6D, adducts with hydroxypropyl acrylate 86280-89-9 95523-89-0, Viscoat 3700 95543-55-8, Isopropyl 4-dimethylaminobenzoate 95567-09-2, Aronix 8100 95567-11-6, Asaflex AFX-810 95567-20-7, Dia Resin Blue P 95567-23-0, Delpet CR-1 95567-50-3, R-526 95567-61-6, Viscoat 823 95971-30-5, 2,4-Diisopropylthioxanthone 108251-12-3, Aronix M-1200 (photoresist compns. containing, dry-film type)

L40 ANSWER 22 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN

ACCESSION NUMBER: 1987:41634 HCAPLUS Full-text

DOCUMENT NUMBER: 106:41634

ORIGINAL REFERENCE NO.: 106:6805a,6808a

TITLE: Fluorene-containing compounds and negative photoresist compositions therefrom

INVENTOR(S): Guillet, James E.; Redpath, Anthony E.

PATENT ASSIGNEE(S): Ecoplastics Ltd., Can.

SOURCE: U.S., 6 pp.

CODEN: USXXAM

DOCUMENT TYPE: Patent

LANGUAGE: English

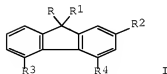
FAMILY ACC. NUM. COUNT: 1

PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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US 4618566	A	19861021	US 1984-666592	19841031
US 4663412	A	19870505	US 1986-881423	19860702
PRIORITY APPLN. INFO.:			US 1984-666592	A3 19841031

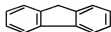
ED Entered STN: 07 Feb 1987

GI



AB Neg. photoresists, sensitive in the 200-300 nm wavelength region, were obtained from crosslinked polymers containing fluorene derivs. I (R-R2 = H, Cl-6 radical, CH2:CMcCO2CH2 or CH2:CMcCO2CHMe; R3, R4 = H, alkyl). Hydrogenation of 2-acetylfluorene gave (2-fluorenyl)ethanol, which, on dehydration, gave 2-vinylfluorene (II). II was then polymerized and tested for UV degradation. The polymer crosslinked upon a 60 s exposure to a 500 W Xe lamp.

IT 86-73-75, Fluorene, derivs., polymers
 (photoresist from)
 RN 86-73-7 HCAPLUS
 CN 9H-Fluorene (CA INDEX NAME)

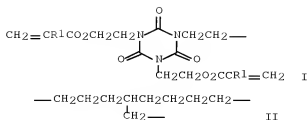


IC ICM G03C001-71
 ICS G03C001-76; C08F008-00
 INCL 430271000
 CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic
 and Other Reprographic Processes)
 ST photoresist elec circuit fluorene deriv
 IT Electric circuits
 (micro-, fluorene derivative-containing polymer photoresist for
 fabrication of)
 IT 86-73-75, Fluorene, derivs., polymers
 (photoresist from)
 IT 31810-15-8P, 2-Vinyl fluorene polymer 106173-78-8P 106173-79-9P
 (preparation and photoresist from)
 IT 10473-10-6P, 2-Vinyl fluorene 106120-02-9P
 (preparation and polymerization of, for photoresist)
 IT 73048-27-8P
 (preparation of, for photoresist)

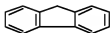
L40 ANSWER 23 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 1986:635832 HCAPLUS Full-text
 DOCUMENT NUMBER: 105:235832
 ORIGINAL REFERENCE NO.: 105:37941a, 37944a
 TITLE: New photopolymerization resin laminates
 INVENTOR(S): Ikeda, Akihiko; Matsuoka, Yoshio; Ai, Hideo
 PATENT ASSIGNEE(S): Asahi Chemical Industry Co., Ltd., Japan
 SOURCE: Jpn. Kokai Tokkyo Koho, 15 pp.
 CODEN: JKXXAF
 DOCUMENT TYPE: Patent
 LANGUAGE: Japanese
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
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JP 61089846	A	19860508	JP 1984-211400	19841011
PRIORITY APPLN. INFO.:			JP 1984-211400	19841011

ED Entered STN: 26 Dec 1986
 GI



- AB The claimed photopolymer laminate has a photopolymerizable layer composed of (1) a vinyl (co)polymer type binder 5-95, (2) an unsatd. compound of the formula $\text{RO}_2\text{CNH}[Z(\text{NHCO}_2\text{R})\text{NHCO}_2\text{Z1CONH}]_n\text{Z}(\text{NHCO}_2\text{R})_2$ [R = $\text{CH}_2\text{:CR1CO}_2\text{Z}_2$, ($\text{CH}_2\text{:CR1CO}_2\text{CH}_2$) 3CCH_2 , ($\text{CH}_2\text{:CR1CO}_2\text{CH}_2$) 2CH , I; Z = II; Z1 = (CH_2) $m\text{O}$, (CH_2CHR_2) p , $\text{CH}_2\text{CMe}_2\text{CH}_2\text{O}$, $\text{CH}(\text{CH}_2\text{O}_2\text{CCR1}=\text{CH}_2)\text{CH}_2\text{O}_2\text{Z}_3\text{OCH}_2\text{CH}(\text{CH}_2\text{O}_2\text{CCR1}=\text{CH}_2)\text{O}$; Z2 = OZ_4 , NCH_2 , (OCH_2CHR_2) p , $\text{OCH}_2\text{CH}_2(\text{O}_2\text{CCH}_2\text{CH}_2\text{CH}_2\text{CH}_2\text{CH}_2\text{CH}_2)\text{q}$, $\text{OCH}_2\text{CH}_2\text{O}_2\text{C-o-C}_6\text{H}_4\text{CO}_2\text{CH}_2\text{CH}_2$, OCH_2CHR_3 ; Z3 = (CH_2) $m\text{O}$, (CH_2CHR_2) p , $\text{CH}_2\text{CMe}_2\text{CH}_2\text{O}$, $\text{COC}_6\text{H}_4\text{CO}_2$, $\text{CH}_2\text{CHR}_2\text{O-p-C}_6\text{H}_4\text{CMe}_2\text{-p-C}_6\text{H}_4\text{OCHR}_2\text{CH}_2\text{O}$; R1, R2 = H, Me; R3 = allyl, phenyl; Z4 = C1-8 divalent aliphatic hydrocarbon moiety n = 0-5; m = 1-10; p = 1-20; q = 1-5] 5-95 and (3) photopolymn. initiator 0.01-30 weight%. The photopolymer laminate is especially useful as a dry film resist for printed plate fabrication.
- IT 86-73-7
(photopolymn. initiator, for dry film photoresist)
- RN 86-73-7 HCAPLUS
- CN 9H-Fluorene (CA INDEX NAME)



- IC ICM B32B027-00
- ICA B32B027-30; H05K003-00
- CC 74-5 (Radiation Chemistry, Photochemistry, and Photographic and Other Reprographic Processes)
Section cross-reference(s): 76
- ST photoresist dry film elec circuit; vinyl polymer
photoresist; urethane acrylate crosslinking agent
photoresist
- IT Electric circuits
(printed, dry film photoresists for fabrication of)
- IT 86-73-7 90-94-8 119-61-9, uses and miscellaneous
24650-42-8 79044-56-7 95543-55-8
(photopolymn. initiator, for dry film photoresist)
- IT 3524-68-3 68224-34-0 72928-42-8 95523-89-0
(photoresist composition containing)
- IT 9011-14-7 25852-37-3 95567-11-6 95567-23-0
(photoresist composition containing, as binder)
- IT 85287-01-0 85797-50-8 85798-04-5 103709-92-8 105511-11-3
105511-12-4 105511-13-5 105511-14-6 105511-15-7 105511-16-8
105511-17-9 105511-18-0 105527-18-2 105527-25-1 105567-50-8
(prepolymer, dry film photoresist composition containing vinyl

polymers and)

L40 ANSWER 24 OF 24 HCAPLUS COPYRIGHT 2008 ACS on STN
 ACCESSION NUMBER: 1976:502422 HCAPLUS Full-text
 DOCUMENT NUMBER: 85:102422
 ORIGINAL REFERENCE NO.: 85:16341a,16344a
 TITLE: Positive polymer resists
 INVENTOR(S): Cipstein, Edward; Moreau, Wayne M.; Need, Omar U.,
 III
 PATENT ASSIGNEE(S): International Business Machines Corp., USA
 SOURCE: Ger. Offen., 10 pp.
 CODEN: GWXXBX
 DOCUMENT TYPE: Patent
 LANGUAGE: German
 FAMILY ACC. NUM. COUNT: 1
 PATENT INFORMATION:

PATENT NO.	KIND	DATE	APPLICATION NO.	DATE
DE 2536300	A1	19760408	DE 1975-2536300	19750814
PRIORITY APPLN. INFO.:			US 1974-505595	A 19740926

ED Entered STN: 12 May 1984
 AB The depolymn. of polysulfones by light (300-600 nm) or by low-energy electron beams (10-30 keV, $1 + 10^{-7}$ -1 coulomb/cm²) is accelerated by free radical formers (CBr₄) or energy transferring agents, such as 2,4,7-trinitrofluorenone. A suitable solvent for the coating is MeNO₂, as developer (ClC₂H₄)₂, and as solvent to remove the resist PhMe of 50°. Thus, the electron beam sensitivity of a polycyclopentenesulfone resist coating was increased by a factor of 5-10 by addition of 5% CBr₄.
 IT 86-73-7
 (sensitizer, for depolymn. of polysulfone pos. resists)
 RN 86-73-7 HCAPLUS
 CN 9H-Fluorene (CA INDEX NAME)



IC G03F007-10
 CC 74-6 (Radiation Chemistry, Photochemistry, and Photographic Processes)
 ST pos resist sensitization halomethane; electron resist pos sensitization; photoresist pos sensitization
 IT 75-52-5 86-73-7 100-01-6 103-33-3 122-39-4 129-79-3
 275-51-4 507-25-5 558-13-4
 (sensitizer, for depolymn. of polysulfone pos. resists)

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(FILE 'HOME' ENTERED AT 08:51:02 ON 19 NOV 2008)

FILE 'HCAPLUS' ENTERED AT 08:51:11 ON 19 NOV 2008

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L1      1 SEA ABB=ON PLU=ON US20050271971/PN
        SEL RN

FILE 'REGISTRY' ENTERED AT 08:51:45 ON 19 NOV 2008
L2      20 SEA ABB=ON PLU=ON (108-46-3/BI OR 110-87-2/BI OR
        125748-07-4/BI OR 156281-11-7/BI OR 1927-95-3/BI OR
        211427-64-4/BI OR 24424-99-5/BI OR 27955-94-8/BI OR
        29654-55-5/BI OR 5001-18-3/BI OR 5292-43-3/BI OR 623-05-2/B
        I OR 65338-98-9/BI OR 683227-72-7/BI OR 683227-73-8/BI OR
        683227-74-9/BI OR 683227-75-0/BI OR 683227-76-1/BI OR
        75-07-0/BI OR 99181-50-7/BI)
        ACT LEE208/A
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L3      STR
L4      33354 SEA SSS FUL L3
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L5      STR L3
L6      4 SEA SUB=L4 SSS SAM L5
L7      52 SEA SUB=L4 SSS FUL L5
        SAV L7 LEE208E/A
        E C13H10/MF
L8      319 SEA ABB=ON PLU=ON C13H10/MF
        E C15H14/MF
L9      570 SEA ABB=ON PLU=ON C15H14/MF
L10     129991 SEA ABB=ON PLU=ON 1839.6/RID
L11     74 SEA ABB=ON PLU=ON (L8 OR L9) AND L10
L12     4 SEA ABB=ON PLU=ON L11 AND 9,9-DIMETHYL?
L13     3 SEA ABB=ON PLU=ON L12 NOT T/ELS
L14     38 SEA ABB=ON PLU=ON L8 AND L10
L15     17 SEA ABB=ON PLU=ON L14 NOT (D OR T)/ELS
L16     13 SEA ABB=ON PLU=ON L15 NOT RADICAL?
L17     11 SEA ABB=ON PLU=ON L16 NOT LABEL?
        E FLUORENE/CN
L18     1 SEA ABB=ON PLU=ON FLUORENE/CN
L19     4 SEA SSS SAM L5
        D SCA

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FILE 'HCAPLUS' ENTERED AT 09:17:21 ON 19 NOV 2008

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L20     37 SEA ABB=ON PLU=ON L7

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        E C15H14O3/MF
L21     2648 SEA ABB=ON PLU=ON C15H14O3/MF
L22     16 SEA ABB=ON PLU=ON L21 AND L10
        E C13H10O3/MF
L23     873 SEA ABB=ON PLU=ON C13H10O3/MF
L24     6 SEA ABB=ON PLU=ON L23 AND L10
L25     1 SEA ABB=ON PLU=ON L24 AND 9H-FLUORENETRIOL
L26     1 SEA ABB=ON PLU=ON L13 NOT RADICAL?

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FILE 'HCAPLUS' ENTERED AT 09:21:28 ON 19 NOV 2008

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L27     13783 SEA ABB=ON PLU=ON L26 OR L25 OR L18
L28     27 SEA ABB=ON PLU=ON L27 AND (PHOTORESIST? OR PHOTO RESIST?

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10/531,208

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OR LIGHTRESIST? OR LIGHT RESIST?)
L29      14 SEA ABB=ON PLU=ON L28 AND PHOTOG?/SC, SX
L30      0 SEA ABB=ON PLU=ON L20 AND (PHOTORESIST? OR PHOTO RESIST?
OR LIGHTRESIST? OR LIGHT RESIST?)
L31      7 SEA ABB=ON PLU=ON L20 AND PHOTOG?/SC, SX
L32      37 SEA ABB=ON PLU=ON L20 OR L30 OR L31
L33      51 SEA ABB=ON PLU=ON L29 OR L32
L34      22 SEA ABB=ON PLU=ON L20 AND RACT/RL
L35      22 SEA ABB=ON PLU=ON L34 AND PREP/RL

FILE 'REGISTRY' ENTERED AT 09:25:34 ON 19 NOV 2008
L36      12 SEA ABB=ON PLU=ON L7 NOT N/ELS

FILE 'HCAPLUS' ENTERED AT 09:28:28 ON 19 NOV 2008
L37      10 SEA ABB=ON PLU=ON L36
L38      2 SEA ABB=ON PLU=ON L37 AND L31
L39      24 SEA ABB=ON PLU=ON L29 OR L37
L40      24 SEA ABB=ON PLU=ON L38 OR

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